SUBSTRATE PROCESSING DEVICE

ABSTRACT

In one exemplary embodiment, a substrate processing apparatus is provided. The substrate processing apparatus includes a processing chamber, a substrate support, a plurality of supply pipes, one or more recovery pipes, one or more flow rate controllers, and a controller. The substrate support includes an upper surface, a lower surface, and one or more partition walls. The one or more partition walls and the lower surface define one or more spaces. The plurality of supply pipes each have an open end. The open end is disposed in a corresponding one of the one or more spaces. The one or more recovery pipes are connected to the one or more spaces, respectively. The one or more partition walls include an outer peripheral wall. The one or more spaces include one space in which the open end of each of two or more supply pipes among the plurality of supply pipes is disposed.

Fig. 7